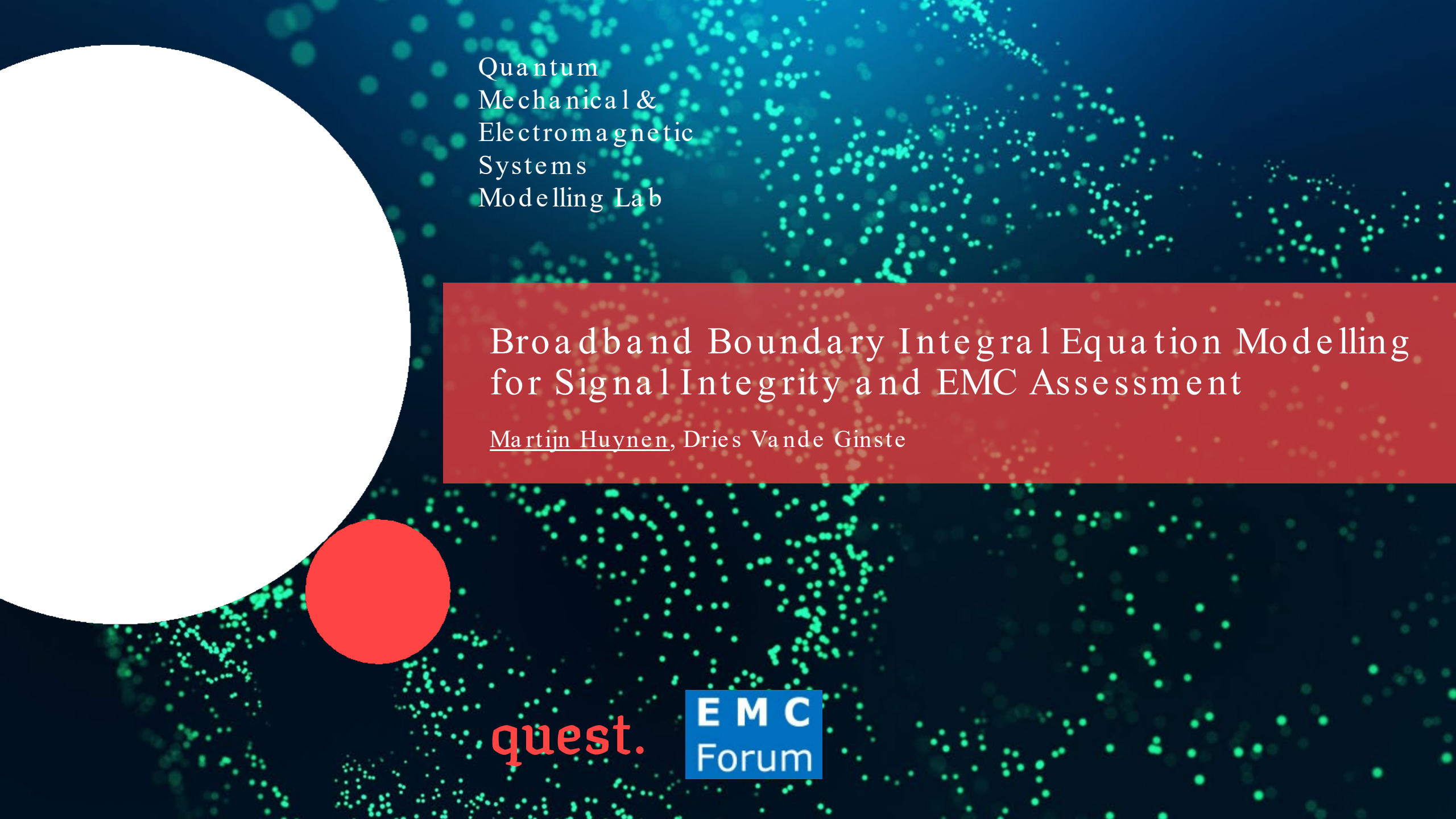




Quantum
Mechanical &
Electromagnetic
Systems
Modelling Lab

Broadband Boundary Integral Equation Modelling for Signal Integrity and EMC Assessment

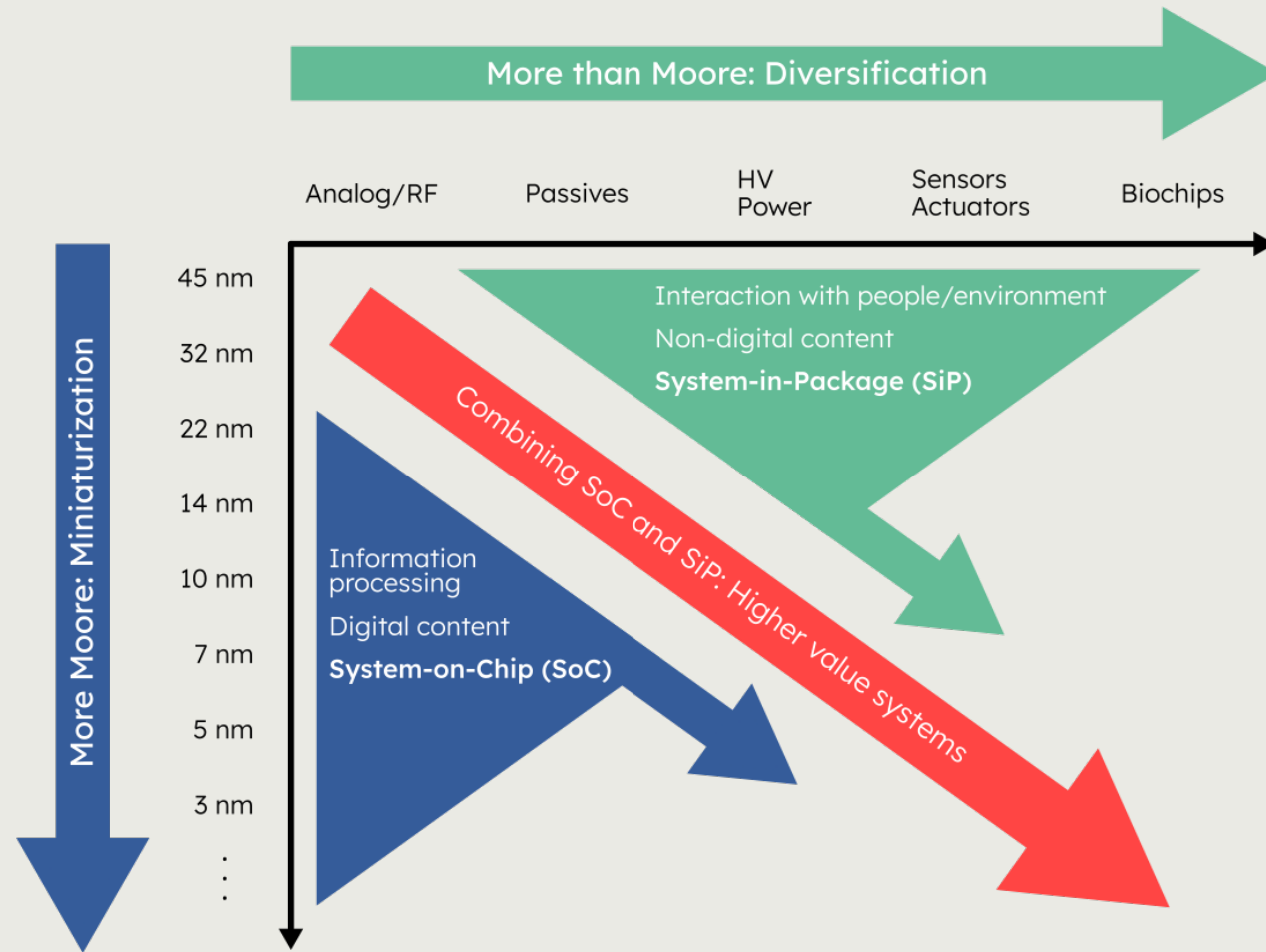
Martijn Huynen, Dries Vande Ginste

quest.

EMC
Forum

Research context at quest

Roadmap for semiconductors.



Research context at quest

Moore, Moorer, Moorest.

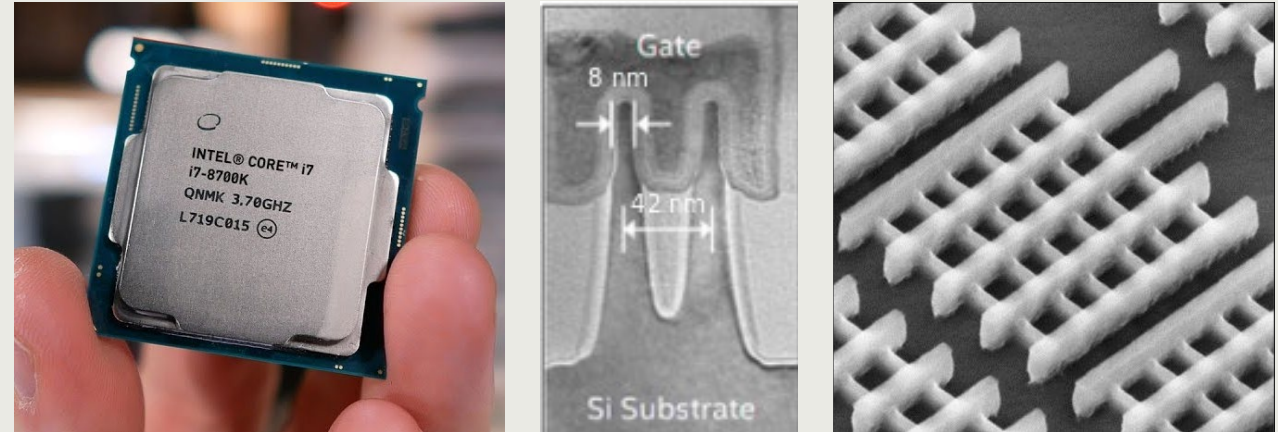
Modeling challenges

Electromagnetic (EM) full -wave

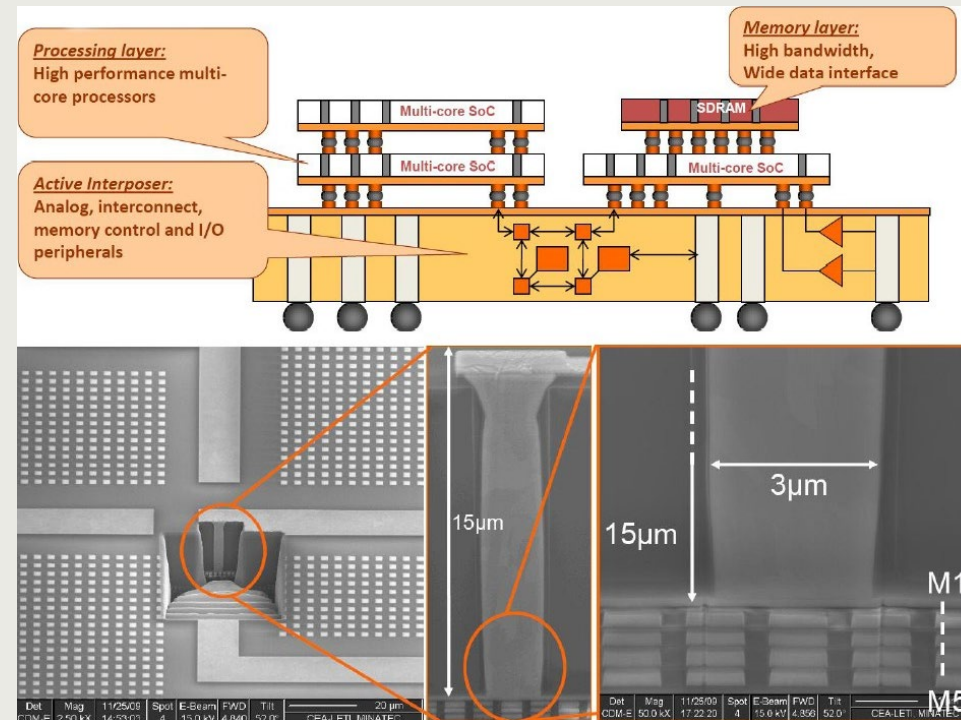
Heterogeneity

Highly multiscale

example 1: Intel's Core i7-8700K processor with tri-gate transistor technology



example 2: 3-D integration (source: CEA-Leti's 2015 roadmap)



Research context at quest

Moore, Moorer, Moorest.

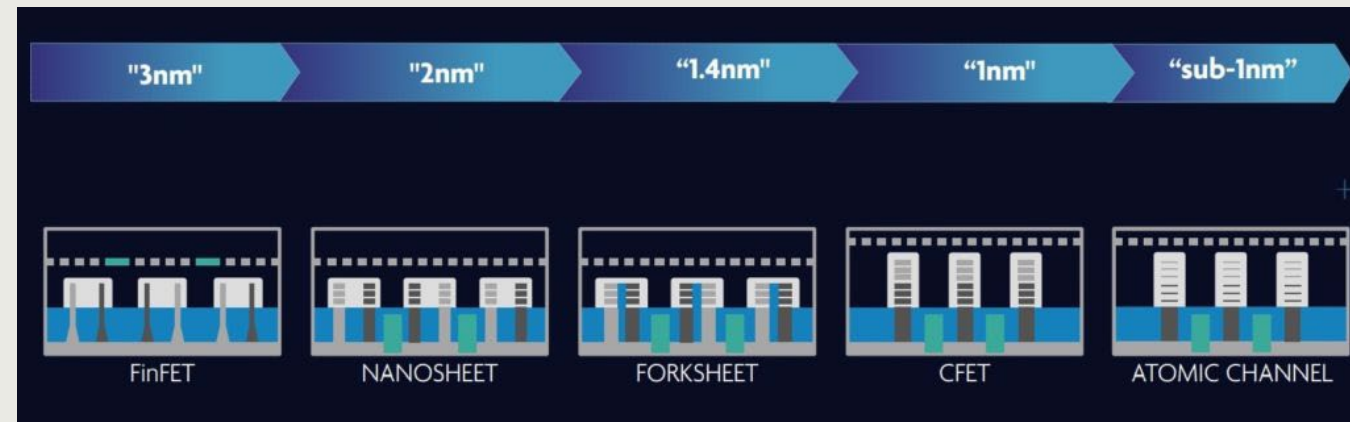
Physical phenomena

- Charge carrier confinement, ballistic transport
- Tunnel effect, Klein effect, ...

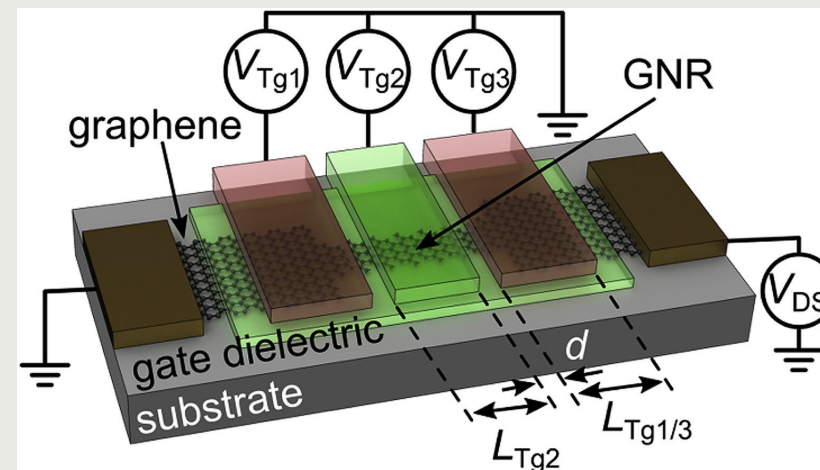
Modeling challenges

- Quantum mechanical (QM) aspects
- Ab Initio* ($\leftrightarrow$ macroscopic conductivity models)
- Multiphysics (QM/EM)

example 3: imec's Transistor Technology Roadmap (Source: imec, 2022)



example 4: Sub-10 nm graphene nano-ribbon tunnel field-effect transistor



Research context at quest

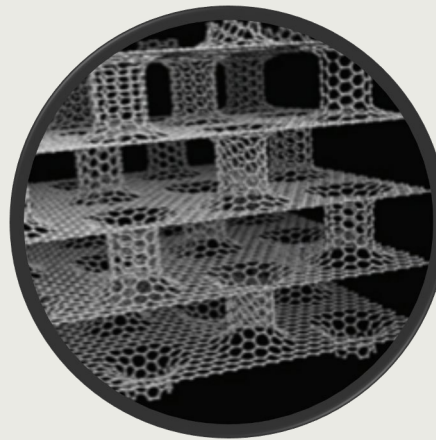
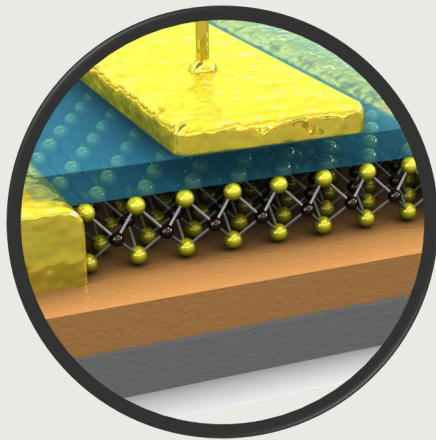
Why do we construct (multiscale and multiphysics) computational techniques?

Electronic, nano- and quantum devices: heavily researched (applications / manufacturability)

Physical phenomena occurring in these devices are not always well -understood

Computational tools and models lead to

a more thorough insight in the functioning of these novel devices and systems;
computer aided design software , avoiding trial and error during development.



Research context at quest

Modeling of interconnects structures (on -PCB and on -chip).

Wish list

heterogenous (dielectric and magnetic) materials

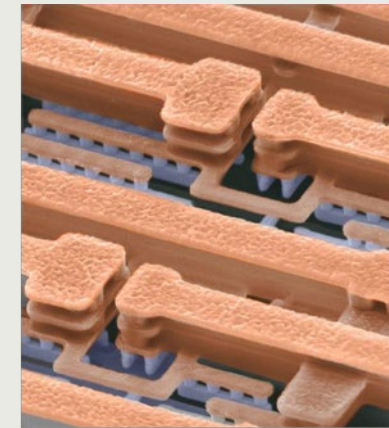
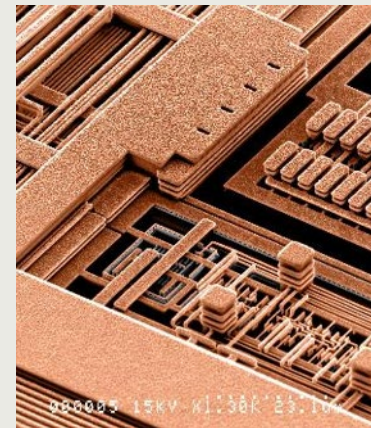
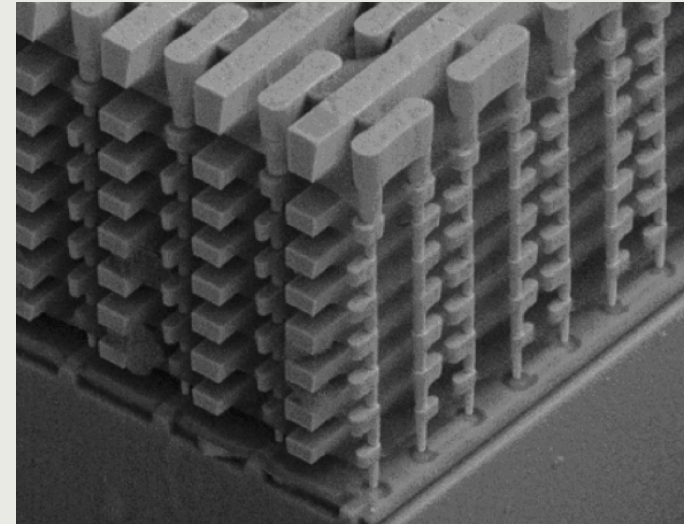
good conductors -> skin effect, proximity effect

semiconductors -> slow-wave effect

full-wave -> accuracy and electromagnetic interference (EMI)

broadband -> signal integrity analysis

efficient



Full-wave broadband characterisation

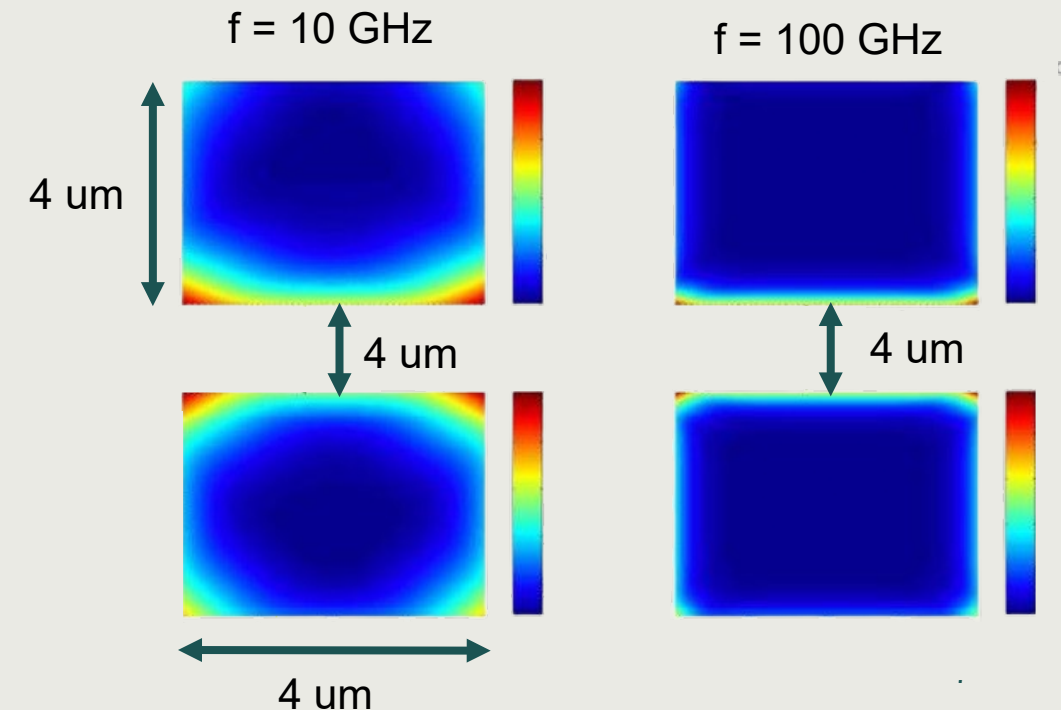
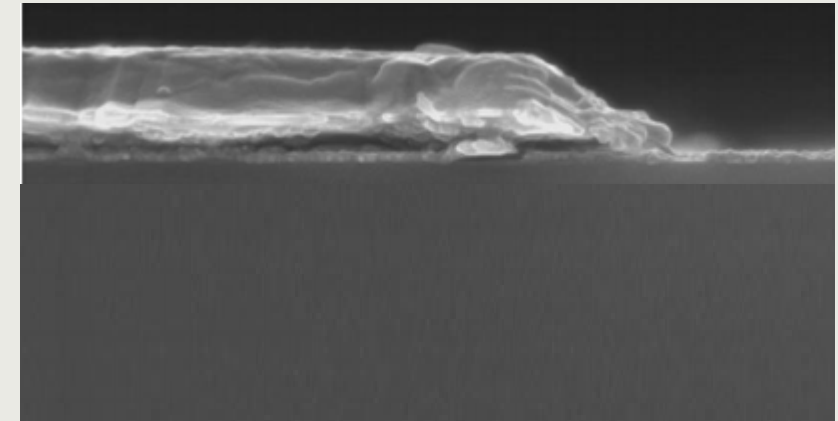
Modeling of interconnects structures (on -PCB and on -chip).

Miniaturization & increased operating frequency ask for **more accurate** and complete **modeling**

(Un)wanted **intricate** geometric **details** become increasingly impactful

Full wave solvers indispensable to capture effects such as the **skin effect** or the proximity effect

Challenging materials such as semiconductors or magnetic materials often **not accurately modeled** over large frequency ranges in (commercial) solvers



Computational electromagnetic techniques

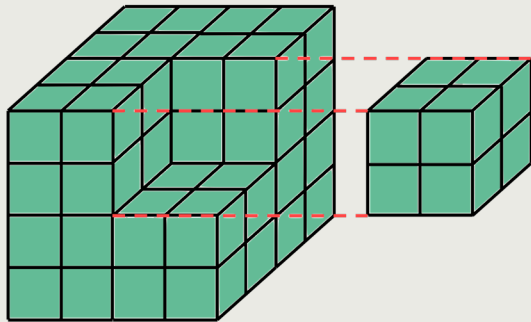
Boundary integral equations

Volumetric methods

Finite element method (FEM), finite-difference time-domain (FDTD),...

Large number of unknowns
with **sparse system** matrix

Difficult to model **EM phenomena** such as skin effect, slow-wave effect,...

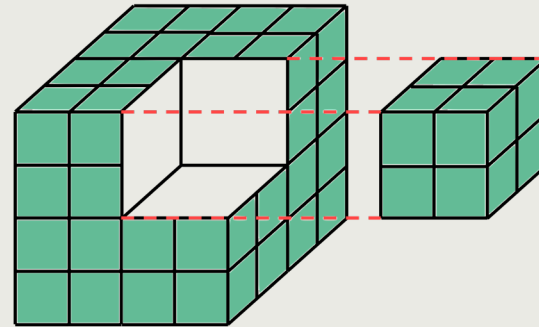


Boundary methods

Boundary element methods (BEM), boundary integral equations (BIE)

Smaller number of unknowns
with **dense system** matrix

Difficulties with modeling **vias, good conductors**, skin effect, ...



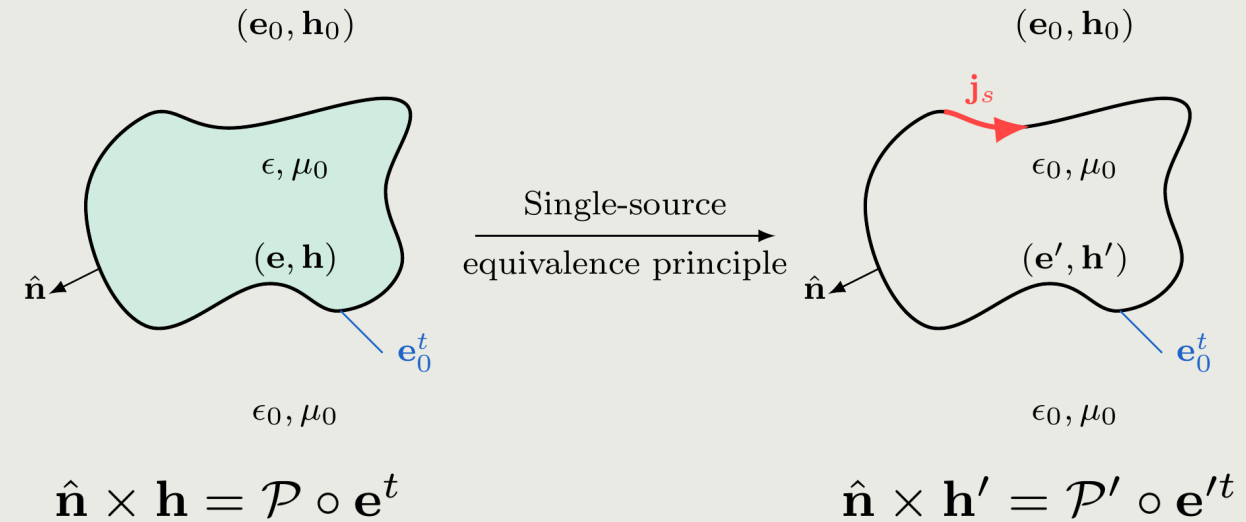
Differential surface admittance operator
overcomes these difficulties!



Boundary integral equations

The Differential Surface Admittance operator

One way to find an expression for $\mathbf{j}_s$ is to introduce the Poincaré-Steklov operator in both situations



Imposing the boundary conditions, we then find an expression for the surface current density as

$$\mathbf{j}_s = (\mathcal{P} - \mathcal{P}') \circ \mathbf{e}_0^t = \mathcal{Y} \circ \mathbf{e}_0^t$$

Leading to the general definition of the **Differential Surface Admittance (DSA) operator**,

which can be integrated into a standard **Electric Field Integral Equation (EFIE)**

$$\hat{\mathbf{n}} \times \mathbf{e}_0^t(\mathbf{r}) = \hat{\mathbf{n}} \times \mathbf{e}_{\text{inc}} - j\omega\mu_0 \hat{\mathbf{n}} \times \int_S \overline{\overline{G_0}}(|\mathbf{r} - \mathbf{r}'|) \mathbf{j}_s(\mathbf{r}') d\mathbf{r}'$$



Boundary integral equations

The Differential Surface Admittance operator

How to construct $\mathcal{Y}$

Through the traditional operators T and K

Most general formulation

Re-introduces Green's function in the (conductive) medium

Through the eigenmodes of the volume

Fully analytical $\rightarrow$ fast and accurate

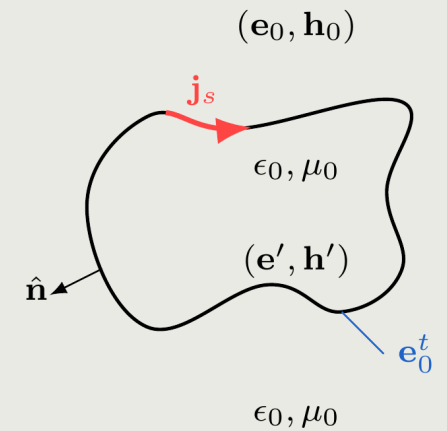
Quite restrictive in terms of geometry

Through the Fokas method

Allows for arbitrary polygons

Until recently only available in 2-D, now extended to 3-D

$$\mathbf{j}_s = (\mathcal{P} - \mathcal{P}') \circ \mathbf{e}_0^t = \mathcal{Y} \circ \mathbf{e}_0^t$$

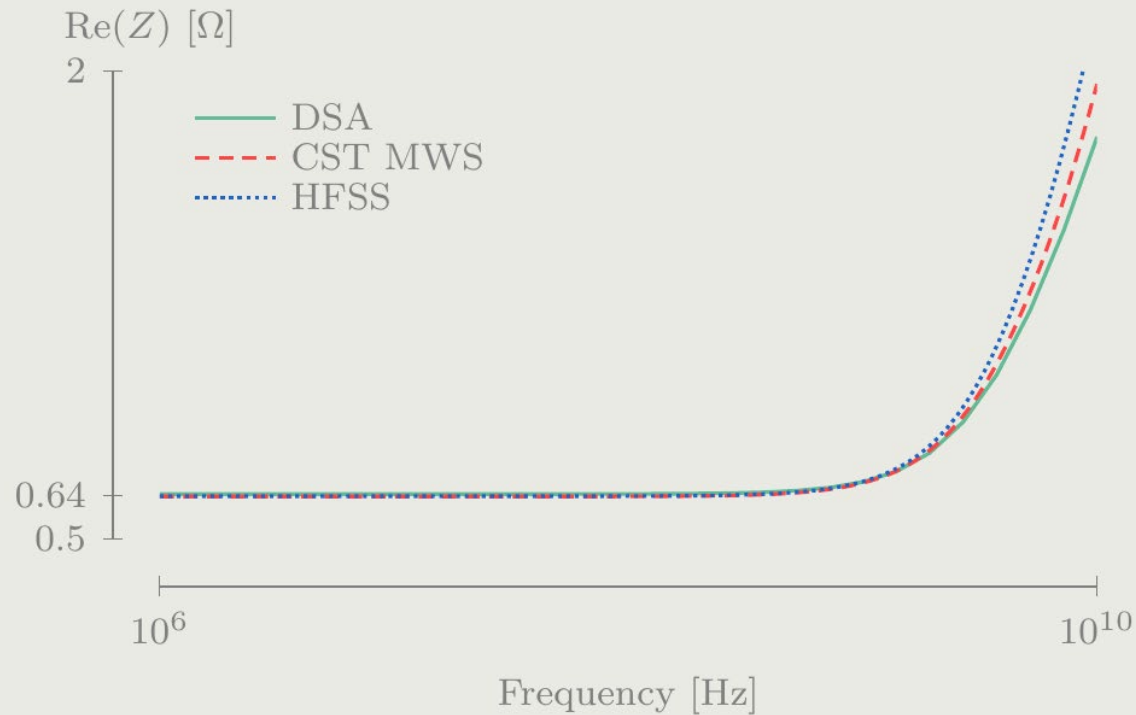
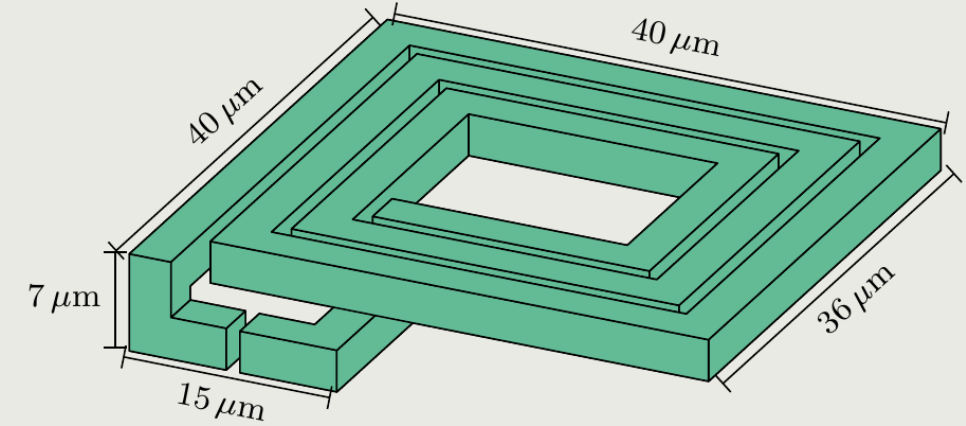


Skin effect in commercial solvers

Broadband simulation of a copper coil

Copper coil with 3x3 μm cross -section

The expected $\sqrt{f}$ slope is not reproduced by the commercial solvers

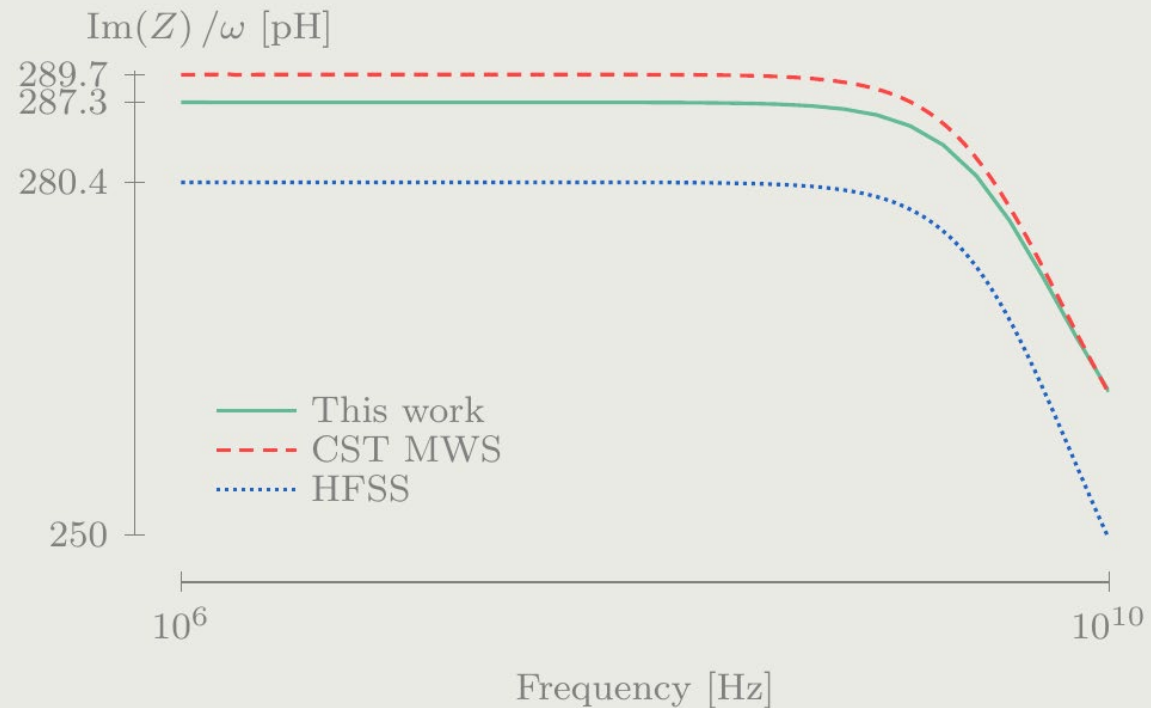
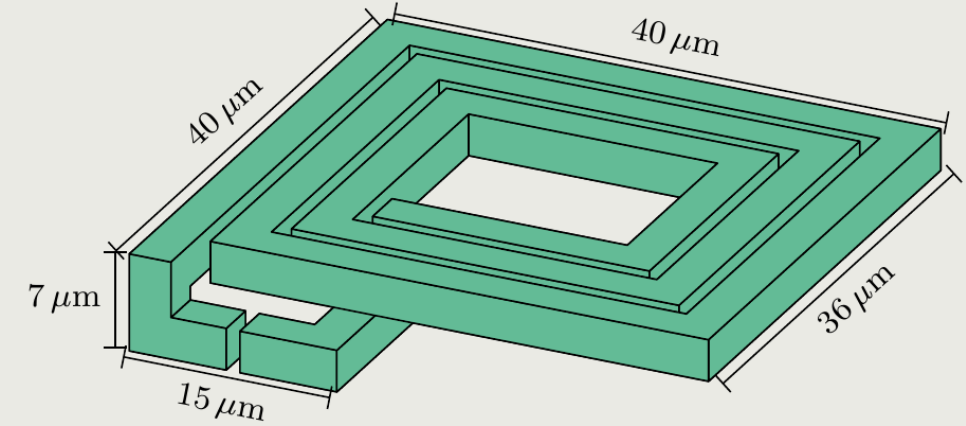


Skin effect in commercial solvers

Broadband simulation of a copper coil

Boundary box settings have a large impact on the inductance calculation

Downside of volumetric based methods



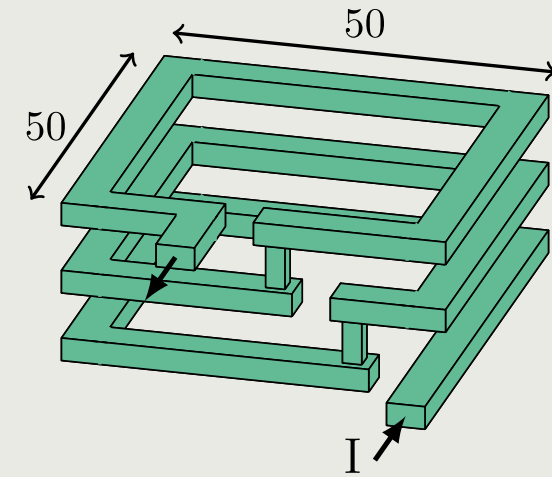
Skin effect in commercial solvers

Stacked spiral on -chip inductor

Key component for various applications in radio frequency and mixed -signal integrated circuits

Material choices reflect typical on -chip integration practices

■ Cu ($\sigma = 5.8 \times 10^7$ S/m)
□ SiO₂ ($\epsilon_r = 3.9$, $\tan\delta = 0.001$)



Dimensions in μm



Skin effect in commercial solvers

Stacked spiral on -chip inductor

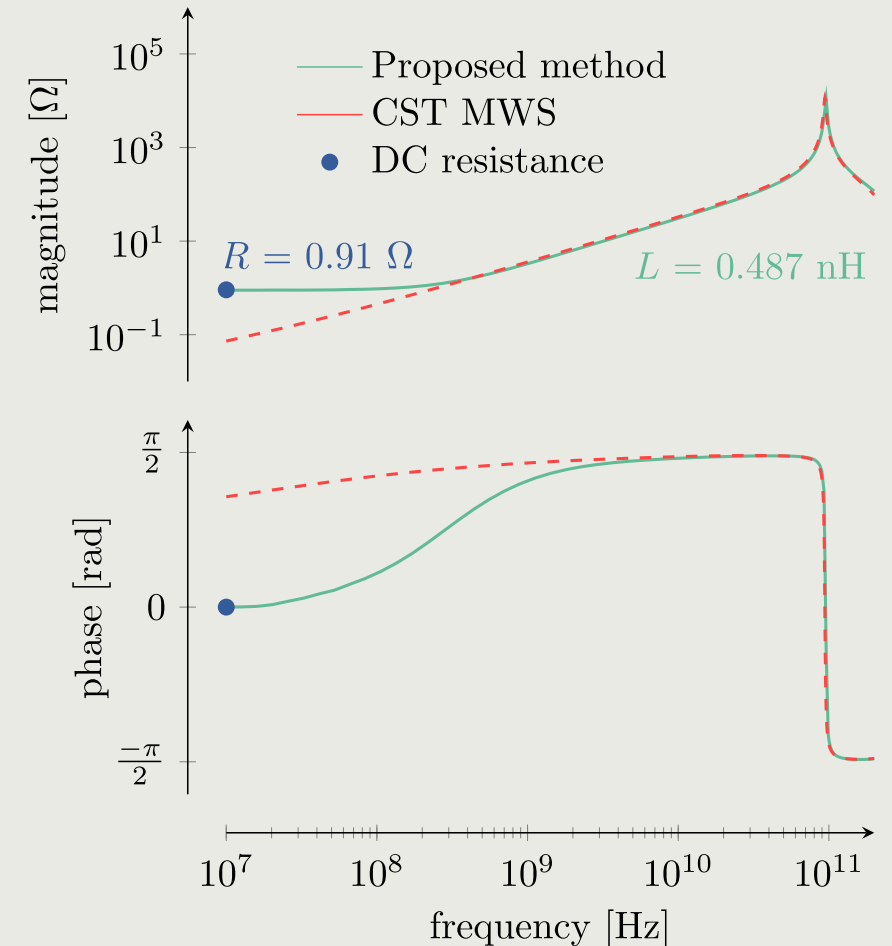
Validation with:

1. CST MWS
2. DC resistance (static solver)

Excellent agreement with CST MWS in inductive and self-resonant region

Converges to DC resistance at lower frequencies

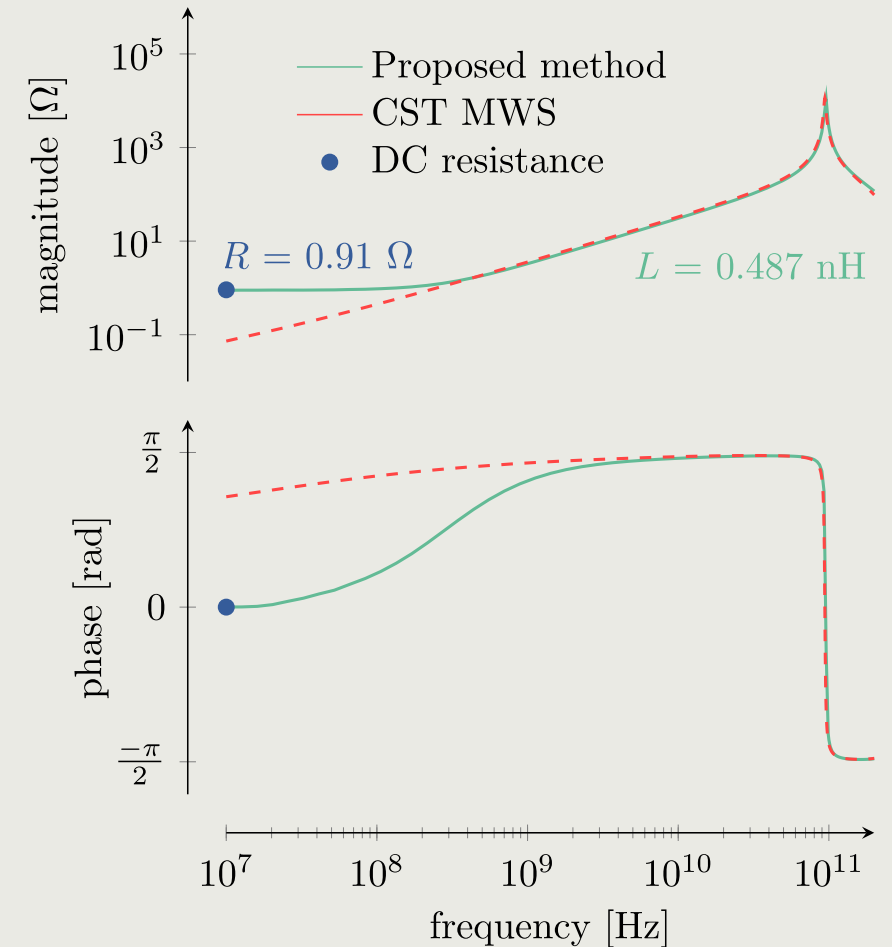
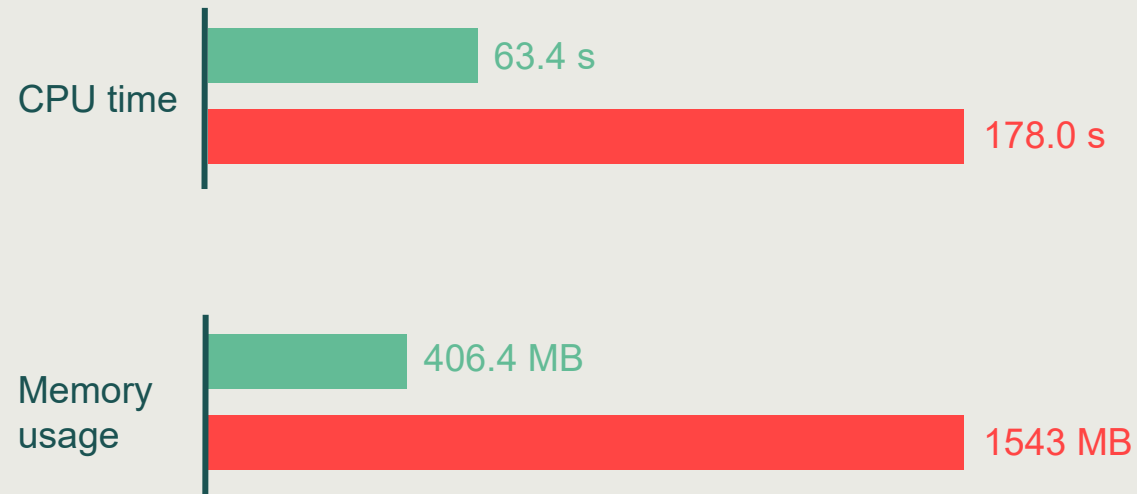
CST MWS was unable to accurately predict the DC resistance



Skin effect in commercial solvers

Stacked spiral on -chip inductor

Significant improvement in computational efficiency
(per frequency point)



Etching effects

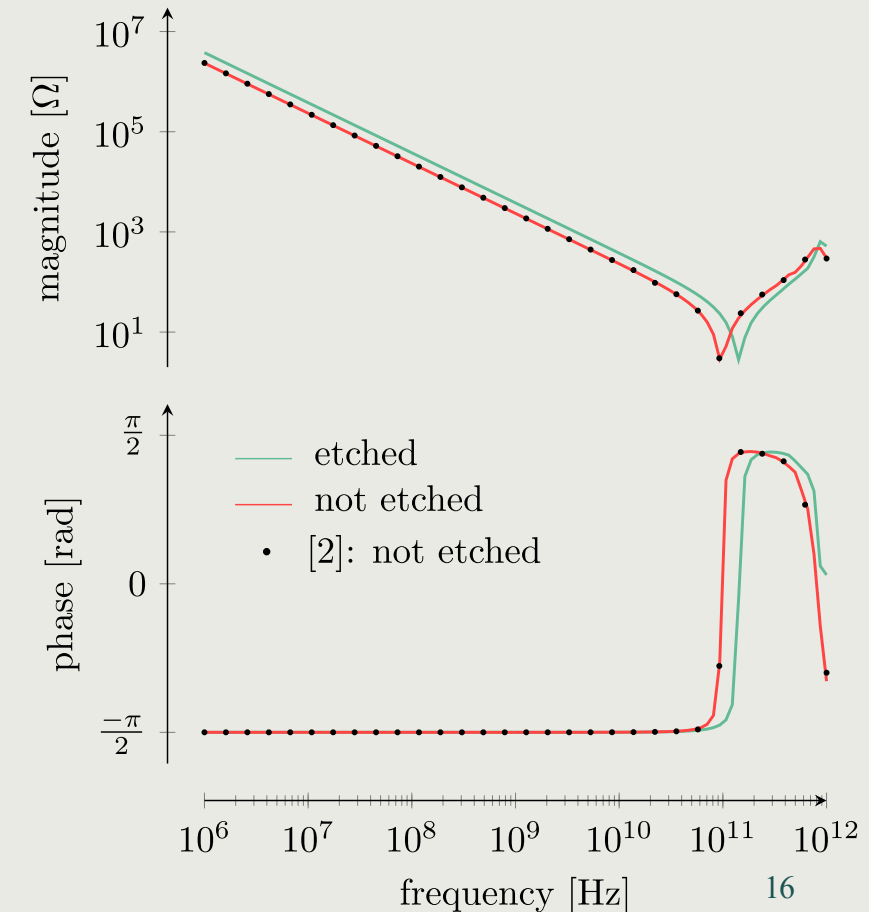
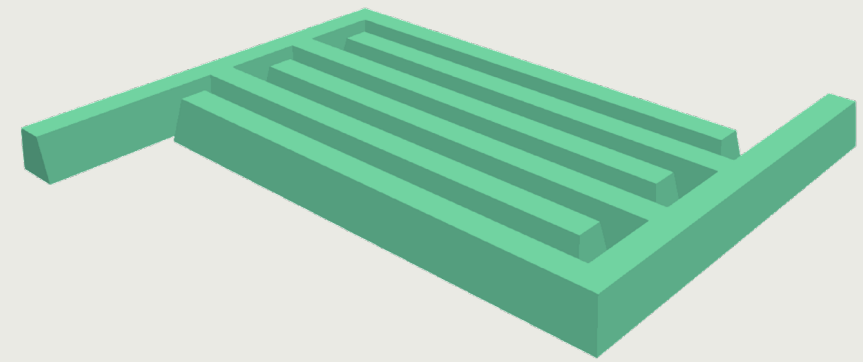
Interdigital capacitor for on-chip applications

50 μm by 50 μm capacitor with 1 μm gap between the digits

Square cross-section vs. etching angle of 78°

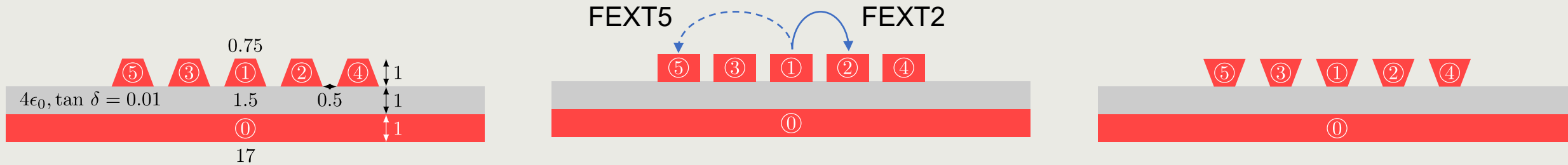
Etching **reduces** capacitance by 38.3 %

High-frequency behavior, i.e., self-resonance, is also impacted

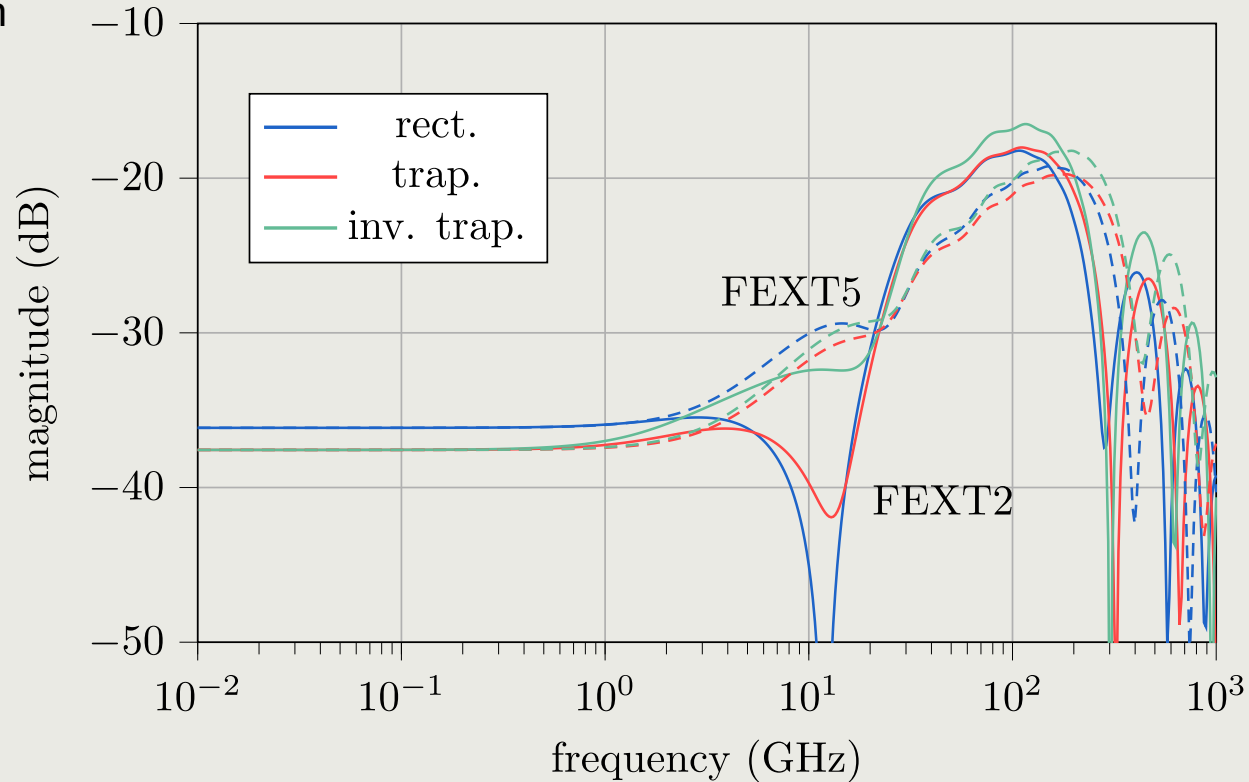


Etching effects

Far-end cross-talk (FEXT) in multiconductor TL strongly depends on conductor's shape

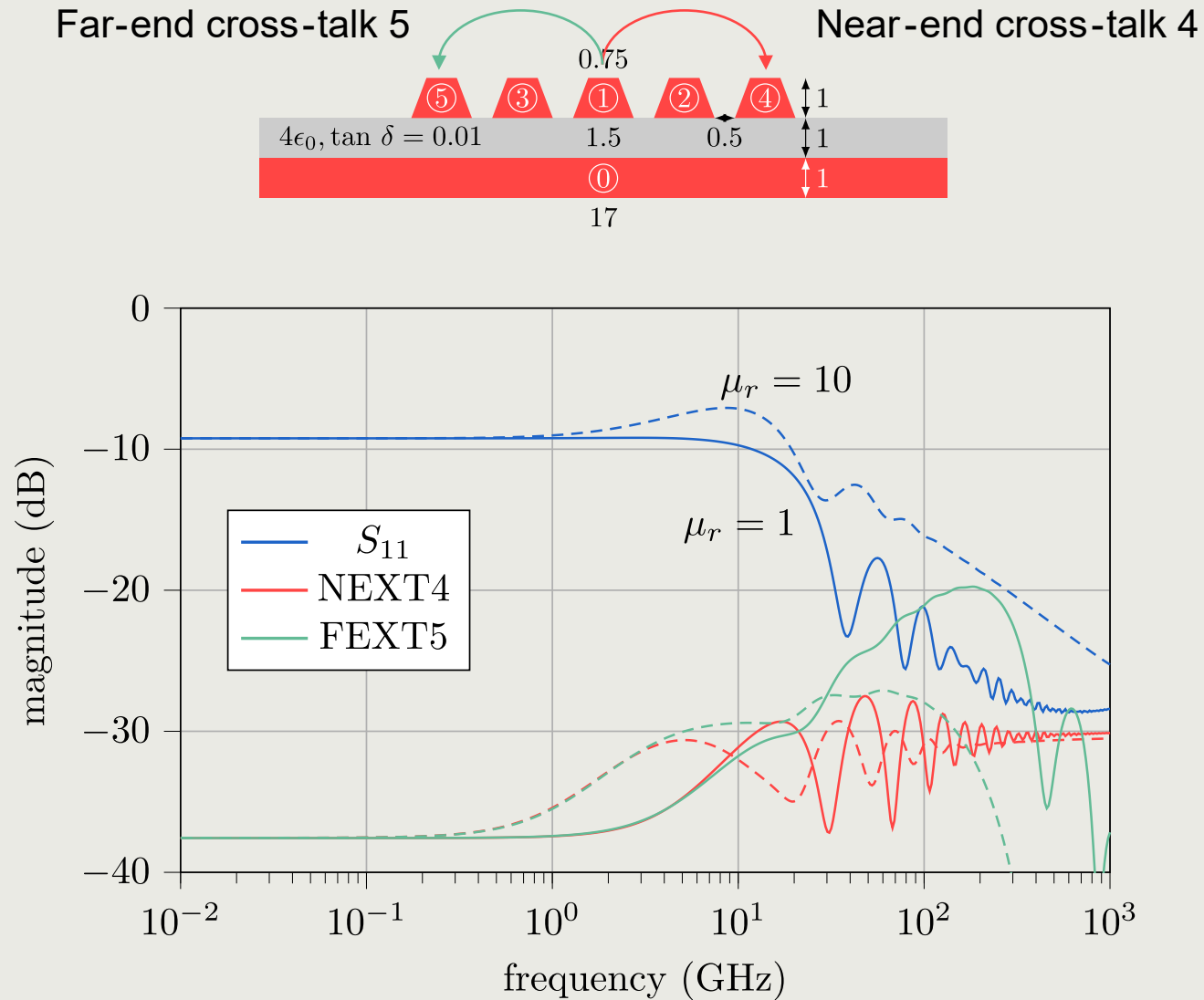


Dimensions in μm



Magnetic materials

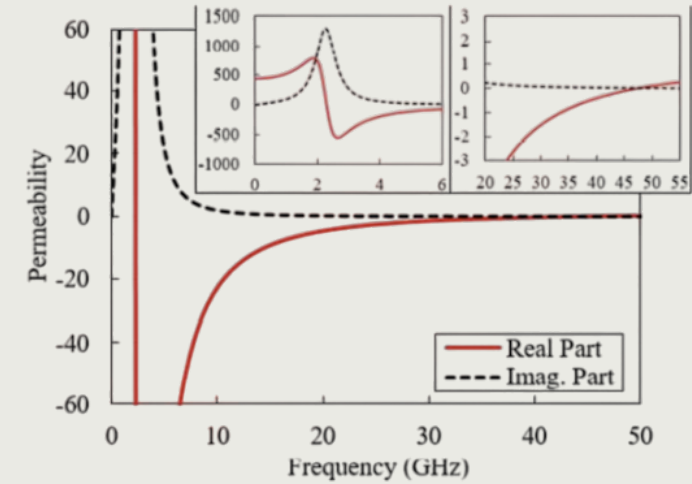
Magnetic materials heavily impact the signal integrity performance



Magnetic materials

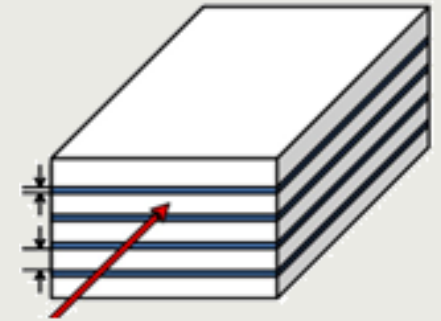
Alternating magnetic and non-magnetic conductors can reduce the skin effect

Materials such as cobalt exhibit a **negative permeability** in certain frequency ranges



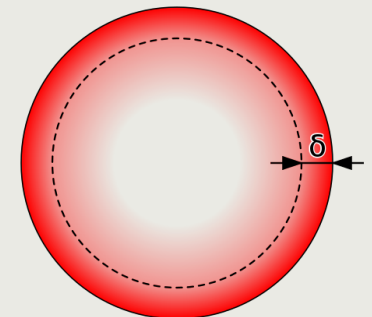
Alternating layers of non-magnetic conductors and magnetic material will exhibit a **lower average** $\mu_r < 1$ or even $\mu_r = 0$

$$\mu_{r,av} = \frac{1 \cdot t_{cu} + \mu_{r,mag} \cdot t_{mag}}{t_{cu} + t_{mag}}$$



This **reduces the skin effect** and hence losses in interconnects

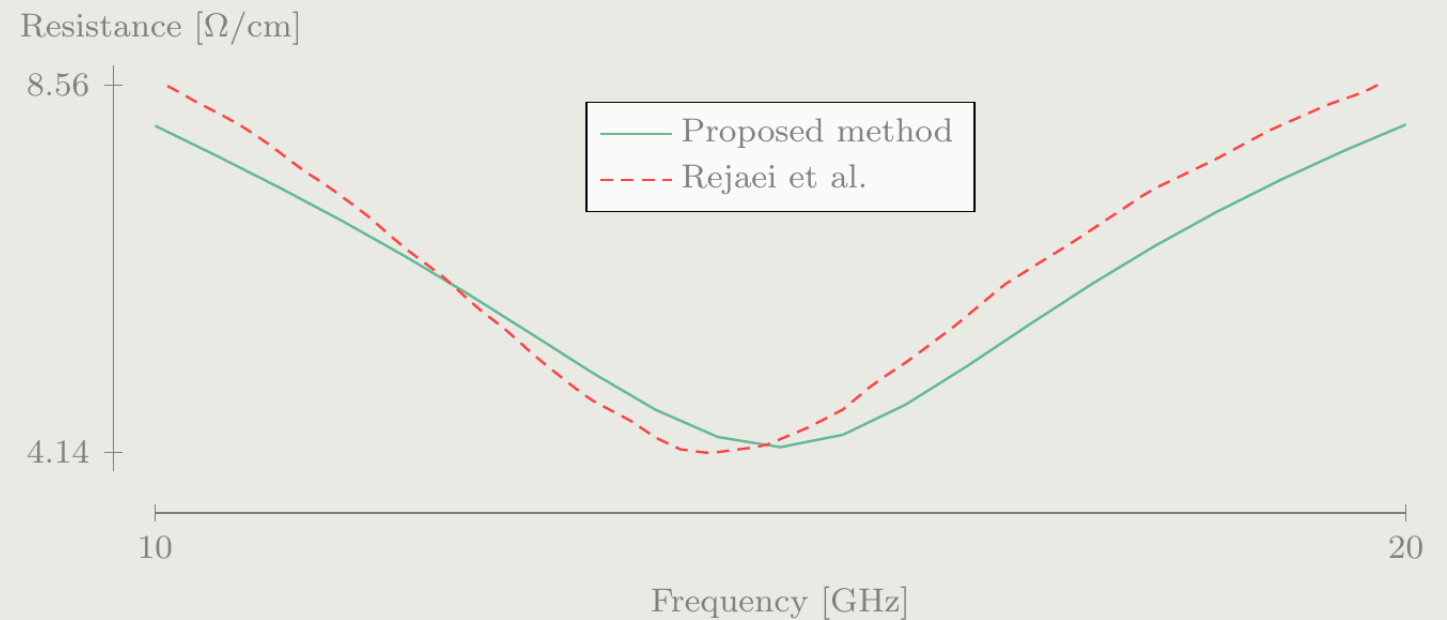
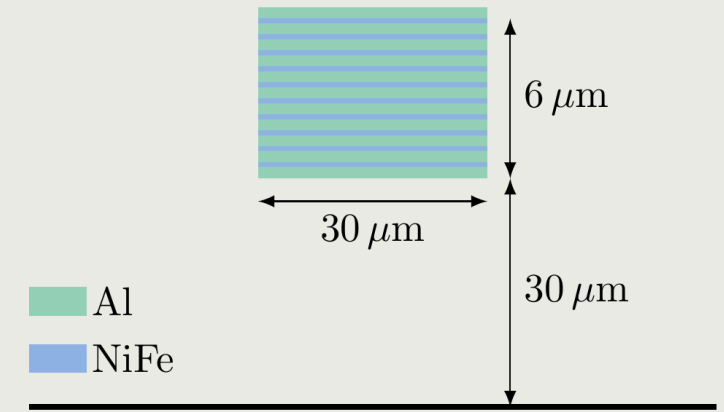
$$\delta = \sqrt{\frac{2}{\omega \sigma \mu_0 \mu_r}}$$



Magnetic materials

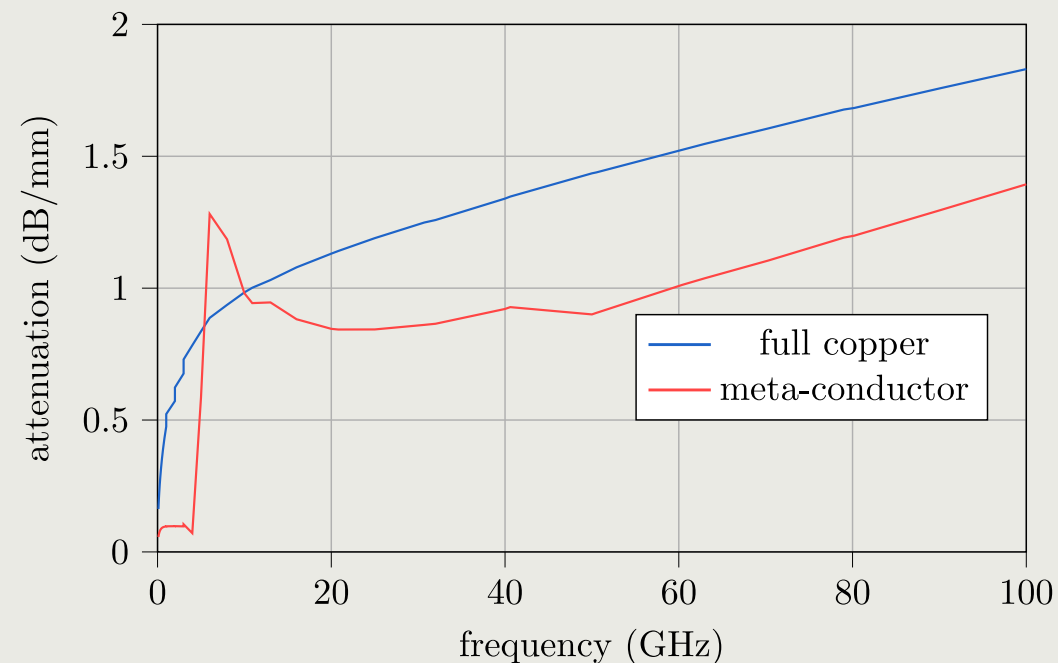
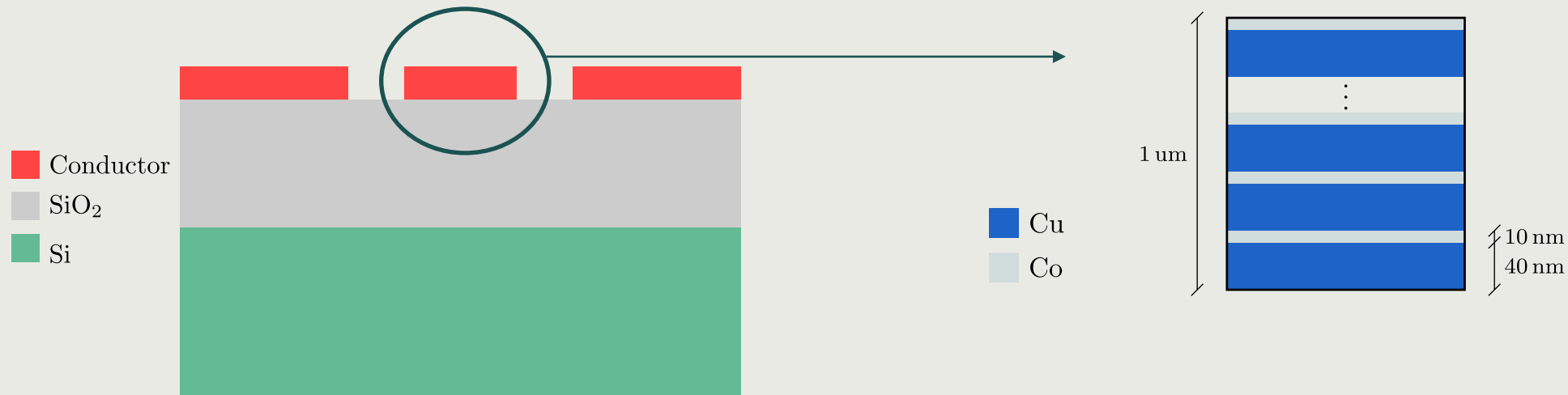
The reduced skin effect reduces the resistance of the combined stack

Microstrip line with metaconductor stack of aluminium and nickel-iron



Magnetic materials

The reduced skin effect significantly lowers the attenuation over a large frequency range



Conclusions

The inclusion of good but **lossy conductors** is a **challenge** for computational methods, including boundary integral equation formulations

Various **approaches** exist of which the **differential surface admittance operator** presents an interesting **alternative** with its own benefits

The DSA formulations exhibit a very **accurate broadband** capturing of a developing **skin-effect**, enabling high-quality **signal integrity analysis**

Additionally, it provides a **flexible alternative** with strong performance for innovative, emerging **interconnect topologies** and **passive components**



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Name SURNAME, Job Title.



imec